CPC COOPERATIVE PATENT CLASSIFICATION

G PHYSICS

(NOTES omitted)

INSTRUMENTS

G11 INFORMATION STORAGE

G11C STATIC STORES (semiconductor memory devices H10B)

NOTES

- 1. This subclass <u>covers</u> devices or arrangements for storage of digital or analogue information:
 - in which no relative movement takes place between an information storage element and a transducer;
 - · which incorporate a selecting-device for writing-in or reading-out the information into or from the store.
- 2. This subclass <u>does not cover</u> elements not adapted for storage and not provided with such means as referred to in Note (3) below, which elements are classified in the appropriate subclass, e.g. of <u>H01</u>, <u>H03K</u>.
- 3. In this subclass, the following terms are used with the meaning indicated:
 - "storage element" is an element which can hold at least one item of information and is provided with means for writing-in or reading-out this information;
 - "memory" is a device, including storage elements, which can hold information to be extracted when desired.

WARNINGS

1. The following IPC groups are not in the CPC scheme. The subject matter for these IPC groups is classified in the following CPC groups:

G11C 8/02	covered by	G11C 8/00, H03K 17/00
G11C 11/4193	covered by	<u>G11C 11/00</u>
G11C 11/4195	covered by	G11C 11/00
G11C 11/4197	covered by	G11C 11/00

2. In this subclass non-limiting references (in the sense of paragraph 39 of the Guide to the IPC) may still be displayed in the scheme.

5/00	Details of stores covered by group G11C 11/00	5/14	• Power supply arrangements {, e.g. power down,
5/005	 {Circuit means for protection against loss of information of semiconductor storage devices} 		chip selection or deselection, layout of wirings or power grids, or multiple supply levels}
5/02	• Disposition of storage elements, e.g. in the form of a	5/141	• • {Battery and back-up supplies}
5/025	matrix array • • {Geometric lay-out considerations of storage-	5/142	 {Contactless power supplies, e.g. RF, induction, or IR}
3,023	and peripheral-blocks in a semiconductor storage	5/143	{Detection of memory cassette insertion
	device (geometrical lay-out of the components in integrated circuits, <u>H01L 27/0207</u>)}		or removal; Continuity checks of supply or ground lines; Detection of supply variations,
5/04	• • Supports for storage elements {, e.g. memory		interruptions or levels (G11C 5/148 takes
	modules}; Mounting or fixing of storage elements on such supports		precedence); Switching between alternative supplies (G11C 5/141 takes precedence)}
5/05	Supporting of cores in matrix	5/144	• • • {Detection of predetermined disconnection or
5/06	 Arrangements for interconnecting storage elements electrically, e.g. by wiring 		reduction of power supply, e.g. power down or power standby }
5/063	• • {Voltage and signal distribution in integrated	5/145	• • {Applications of charge pumps; Boosted voltage
	semi-conductor memory access lines, e.g. word- line, bit-line, cross-over resistance, propagation		circuits; Clamp circuits therefor (G11C 5/141 takes precedence)}
	delay}	5/146	• • • {Substrate bias generators (<u>G11C 5/141</u> takes
5/066	• • {Means for reducing external access-lines for a		precedence)}
	semiconductor memory clip, e.g. by multiplexing	5/147	 Voltage reference generators, voltage or current regulators; Internally lowered supply levels;
5/08	at least address and data signals} for interconnecting magnetic elements, e.g.		Compensation for voltage drops (G11C 5/141
	toroidal cores		takes precedence)}
5/10	for interconnecting capacitors	5/148	• • {Details of power up or power down circuits,
5/12	 Apparatus or processes for interconnecting storage 		standby circuits or recovery circuits}

CPC - 2024.05

elements, e.g. for threading magnetic cores

7/00	Arrangements for writing information into, or	7/1054	{Optical output buffers}
	reading information out from, a digital store	7/1057	• • • {Data output buffers, e.g. comprising level
	(G11C 5/00) takes precedence; auxiliary circuits for	= 40.5	conversion circuits, circuits for adapting load}
	stores using semiconductor devices <u>G11C 11/4063</u> , G11C 11/413)	7/106 7/1063	 {Data output latches} {Control signal output circuits, e.g. status or
7/005	• {with combined beam-and individual cell access}	7/1003	busy flags, feedback command signals}
7/02	 with means for avoiding parasitic signals 	7/1066	• • • {Output synchronization}
7/04	. with means for avoiding disturbances due to	7/1069	• • • {I/O lines read out arrangements}
7/06	temperature effects	7/1072	• • {for memories with random access ports
7/06	• Sense amplifiers; Associated circuits {, e.g. timing or triggering circuits}		synchronised on clock signal pulse trains, e.g. synchronous memories, self timed memories}
7/062	• • {Differential amplifiers of non-latching type, e.g. comparators, long-tailed pairs}	7/1075	• • {for multiport memories each having random access ports and serial ports, e.g. video RAM}
7/065	• • {Differential amplifiers of latching type}	7/1078	• • {Data input circuits, e.g. write amplifiers, data
7/067 7/08	. {Single-ended amplifiers}. Control thereof		input buffers, data input registers, data input level conversion circuits}
7/08	Input/output [I/O] data interface arrangements, e.g.	7/1081	• • {Optical input buffers}
,,10	I/O data control circuits, I/O data buffers	7/1084	• • • {Data input buffers, e.g. comprising level
7/1003	{Interface circuits for daisy chain or ring bus		conversion circuits, circuits for adapting load}
	memory arrangements}	7/1087	{Data input latches}
7/1006	• • {Data managing, e.g. manipulating data before writing or reading out, data bus switches or	7/109	{Control signal input circuits}
	control circuits therefor}	7/1093 7/1096	 {Input synchronization} {Write circuits, e.g. I/O line write drivers}
7/1009	• • {Data masking during input/output}	7/1090	Bit line control circuits, e.g. drivers, boosters, pull-
7/1012	• • {Data reordering during input/output, e.g.	7/12	up circuits, pull-down circuits, precharging circuits,
	crossbars, layers of multiplexers, shifting or		equalising circuits, for bit lines
7/1015	rotating}	7/14	Dummy cell management; Sense reference voltage
7/1015	 {Read-write modes for single port memories, i.e. having either a random port or a serial port} 	7/16	generators
7/1018	• • {Serial bit line access mode, e.g. using bit line	//10	Storage of analogue signals in digital stores using an arrangement comprising analogue/digital [A/D]
	address shift registers, bit line address counters,		converters, digital memories and digital/analogue
7/1021	bit line burst counters}		[D/A] converters
7/1021	• • • • {Page serial bit line access mode, i.e. using an enabled row address stroke pulse with its	7/18	Bit line organisation; Bit line lay-out
	associated word line address and a sequence	7/20	 Memory cell initialisation circuits, e.g. when powering up or down, memory clear, latent image
	of enabled column address stroke pulses each		memory
	with its associated bit line address}	7/22	• Read-write [R-W] timing or clocking circuits;
7/1024	• • • • • {Extended data output [EDO] mode, i.e. keeping output buffer enabled during an		Read-write [R-W] control signal generators or
	extended period of time}	7/000	management
7/1027	{Static column decode serial bit line access	7/222	 {Clock generating, synchronizing or distributing circuits within memory device}
	mode, i.e. using an enabled row address	7/225	{Clock input buffers}
	stroke pulse with its associated word line	7/227	• • {Timing of memory operations based on dummy
	address and a sequence of enabled bit line addresses}		memory elements or replica circuits}
7/103	• • • {using serially addressed read-write data	7/24	. Memory cell safety or protection circuits, e.g.
	registers (G11C 7/1036 takes precedence)}		arrangements for preventing inadvertent reading or writing; Status cells; Test cells
7/1033	• • • {using data registers of which only one stage		
	is addressed for sequentially outputting data from a predetermined number of stages, e.g.	8/00	Arrangements for selecting an address in a digital store (for stores using transistors G11C 11/407,
	nibble read-write mode}		G11C 11/413)
7/1036	{using data shift registers}	8/005	• {with travelling wave access}
7/1039	• • {using pipelining techniques, i.e. using latches	8/04	• using a sequential addressing device, e.g. shift
	between functional memory parts, e.g. row/		register, counter
7/10/10	column decoders, I/O buffers, sense amplifiers}	8/06	Address interface arrangements, e.g. address buffers
7/1042	• • • {using interleaving techniques, i.e. read-write of one part of the memory while preparing	8/08	 Word line control circuits, e.g. drivers, boosters, pull-up circuits, pull-down circuits, precharging
	another part}		circuits, for word lines
7/1045	{Read-write mode select circuits}	8/10	. Decoders
7/1048	 {Data bus control circuits, e.g. precharging, presetting, equalising} 	8/12	Group selection circuits, e.g. for memory block selection, chip selection, array selection
7/1051		8/14	Word line organisation; Word line lay-out
	data output buffers, data output registers, data		2 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7
	output level conversion circuits}		

one s			
addre	ple access memory array, e.g. addressing torage element via at least two independent essing line groups	11/06085	• • • {Multi-aperture structures or multi-magnetic closed circuits, each aperture storing a "bit", realised by rods, plates, grids, waffle-irons,(i.e.
8/18 . Addr	ess timing or clocking circuits; Address control		grooved plates) or similar devices}
signa	l generation or management, e.g. for row	11/06092	• • • {Multi-aperture structures or multi-magnetic
[CAS	ess strobe [RAS] or column address strobe [S] signals		closed circuits using two or more apertures per bit}
	ess safety or protection circuits, i.e.	11/061	• • using elements with single aperture or magnetic
	gements for preventing unauthorized or		loop for storage, one element per bit, and for
accid	ental access		destructive read-out {(contains no documents,
11/00 Digital	stores characterised by the use of		see G11C 11/06007, G11C 11/06014,
	lar electric or magnetic storage		<u>G11C 11/06021</u> , <u>G11C 11/06028</u>)}
	ts; Storage elements therefor	11/063	bit organised, such as 2 1/2D, 3D
	14/00 - G11C 21/00 take precedence)		organisation, i.e. for selection of an
	• • • • • • • • • • • • • • • • • • • •		element by means of at least two coincident partial currents both for reading and for
NOTE			writing {(contains no documents; see
	up G11C 11/56 takes precedence over groups		G11C 11/06035)}
<u>G11</u>	<u>C 11/02</u> - <u>G11C 11/54</u> .	11/065	• • • word organised, such as 2D organisation, or
{Th	s Note corresponds to IPC Note (1) relating to	11/063	linear selection, i.e. for selection of all the
<u>G11</u>	<u>C 11/02</u> - <u>G11C 11/56</u> .}		elements of a word by means of a single full
44/00=			current for reading {(contains no documents;
	prising combined but independently operative		see G11C 11/06042)}
	I-ROM, RAM-PROM, RAM-EPROM cells}	11/067	using elements with single aperture or
	magnetic elements		magnetic loop for storage, one element
	ng storage elements having cylindrical form,		per bit, and for non-destructive read-
	. rod, wire (<u>G11C 11/12</u> , <u>G11C 11/14</u> take excedence)		out {(contains no documents, see
	ng single-aperture storage elements, e.g. ring		<u>G11C 11/0605</u> - <u>G11C 11/06071</u>)}
	e; using multi-aperture plates in which each	11/08	• using multi-aperture storage elements, e.g.
	lividual aperture forms a storage element		using transfluxors; using plates incorporating
	(using a single aperture or single magnetic		several individual multi-aperture storage elements
	closed circuit}	11/10	(G11C 11/10 takes precedence)
	, and the second	11/10	
	NOTE		using multi-axial storage elements
	NOTE	11/12	• using tensors; using twistors, i.e. elements in
	Provisionally contains the following details;	11/12	• using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted
	Provisionally contains the following details; control write -, read -, address circuitry	11/12 11/14	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00,	11/12	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155)
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature	11/12 11/14 11/15	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence)
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct	11/12 11/14 11/15 11/155	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements	11/12 11/14 11/15	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00,	11/12 11/14 11/15 11/155 11/16	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect
	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements	11/12 11/14 11/15 11/155	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure,
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11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00)	11/12 11/14 11/15 11/155 11/16 11/161	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} {with destructive read-out}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} { with destructive read-out}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} {with destructive read-out} {Matrixes} {Bit core selection for writing or	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1655 11/1657	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} {with destructive read-out} {Matrixes} {Bit core selection for writing or reading, by at least two coincident	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1655 11/1657 11/1659	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {with destructive read-out} . {Matrixes} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised,	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1657 11/1659 11/1673	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits or methods} {Reading or sensing circuits or methods}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {with destructive read-out} {Matrixes} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1657 11/1659 11/1673	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits or methods} {Reading or sensing circuits or methods} {Writing or programming circuits or
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {with destructive read-out} . {Matrixes} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised,	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655 11/1657 11/1673 11/1673	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {With destructive read-out} . {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} {"word"-organised, e.g. 2D	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655 11/1657 11/1673 11/1675	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Verifying circuits or methods} {Timing circuits or methods} {Protection circuits or methods}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {Matrixes} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} {"word"-organised, e.g. 2D organisation or linear selection, i.e.	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655 11/1657 11/1677 11/1673 11/1677 11/1677	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Timing circuits or methods}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} • {with destructive read-out} • { Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} • • • {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} • {with non-destructive read-out}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1655 11/1657 11/1659 11/1673 11/1675 11/1673 11/1675	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Verifying circuits or methods} {Timing circuits or methods} {Protection circuits or methods}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} • {with destructive read-out} • {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} • • {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} • {with non-destructive read-out} • {Matrixes}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1655 11/1657 11/1659 11/1673 11/1675 11/1675 11/1675 11/1693 11/1695 11/1697	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Verifying circuits or methods} {Timing circuits or methods} {Protection circuits} {Power supply circuits}
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} • {with destructive read-out} • • {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} • • • {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} • {with non-destructive read-out} • • {Matrixes} • • • {"bit"-organised (2 1/2D, 3D or	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1657 11/1657 11/1673 11/1675 11/1673 11/1675 11/1677 11/1693 11/1697 11/18	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Verifying circuits or methods} {Protection circuits or methods} {Protection circuits or methods} {Power supply circuits} using Hall-effect devices
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} • {with destructive read-out} • {Matrixes} • • {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} • • {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} • {with non-destructive read-out} • {Matrixes} • • {"bit"-organised (2 1/2D, 3D or similar organisation)}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1657 11/1659 11/1673 11/1677 11/1693 11/1697 11/1697 11/18 11/19	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Verifying circuits or methods} {Timing circuits or methods} {Protection circuits or methods} {Power supply circuits} using Hall-effect devices using non-linear reactive devices in resonant circuits
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {with destructive read-out} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} . {with non-destructive read-out} {Matrixes} {"bit"-organised (2 1/2D, 3D or similar organisation)} {"word"-organised (2D organisation)	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655 11/1657 11/1677 11/1673 11/1675 11/1677 11/1693 11/1697 11/18 11/19 11/20	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Verifying circuits or methods} {Protection circuits or methods} {Protection circuits or methods} using Hall-effect devices using non-linear reactive devices in resonant circuits using parametrons
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {With destructive read-out} . {Matrixes} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} {"word"-organised, e.g. 2D organisation or linear selection through all the bit-cores of a word during reading} . {with non-destructive read-out} . {Matrixes} {"bit"-organised (2 1/2D, 3D or similar organisation)} {"word"-organised (2D organisation or linear selection)}	11/12 11/14 11/15 11/155 11/16 11/161 11/165 11/1653 11/1655 11/1657 11/1677 11/1673 11/1675 11/1677 11/1693 11/1695 11/1697 11/18 11/19 11/20 11/21	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Timing circuits or methods} {Protection circuits or methods} {Power supply circuits} using Hall-effect devices using parametrons using electric elements
11/06014	Provisionally contains the following details; control write -, read -, address circuitry (pulse generators in general H03K 5/00, H03K 17/00); arrangements for temperature compensation; checking of the correct functioning and repair arrangements (checking methods in general G06F 11/00, G06F 11/28; testing magnetic elements per se G01R 33/00); magnetic properties, choice of materials or the like (materials per se H01F 1/00) {using one such element per bit} . {with destructive read-out} {Bit core selection for writing or reading, by at least two coincident partial currents, e.g. "bit"- organised, 2L/2D, or 3D} {"word"-organised, e.g. 2D organisation or linear selection, i.e. full current selection through all the bit-cores of a word during reading} . {with non-destructive read-out} {Matrixes} {"bit"-organised (2 1/2D, 3D or similar organisation)} {"word"-organised (2D organisation)	11/12 11/14 11/15 11/155 11/161 11/161 11/165 11/1653 11/1657 11/1659 11/1677 11/1673 11/1677 11/1693 11/1695 11/1697 11/18 11/19 11/20 11/21 11/22	 using tensors; using twistors, i.e. elements in which one axis of magnetisation is twisted using thin-film elements using multiple magnetic layers (G11C 11/155 takes precedence) with cylindrical configuration using elements in which the storage effect is based on magnetic spin effect {details concerning the memory cell structure, e.g. the layers of the ferromagnetic memory cell} {Auxiliary circuits} {Address circuits or decoders} {Bit-line or column circuits} {Word-line or row circuits} {Cell access} {Reading or sensing circuits or methods} {Writing or programming circuits or methods} {Timing circuits or methods} {Protection circuits or methods} {Protection circuits or methods} yended the first devices using Hall-effect devices using parametrons using electric elements using ferroelectric elements

11/225	• • {Auxiliary circuits}	11/40618 {Refresh operations over multiple banks
11/2253	{Address circuits or decoders}	or interleaving}
11/2255	{Bit-line or column circuits}	11/40622 {Partial refresh of memory arrays}
11/2257	• • • • {Word-line or row circuits}	11/40626 {Temperature related aspects of refresh
11/2259	{Cell access}	operations}
11/2273	• • • {Reading or sensing circuits or methods}	11/4063 Auxiliary circuits, e.g. for addressing,
11/2275	• • • • {Writing or programming circuits or	decoding, driving, writing, sensing or
	methods}	timing
11/2277	• • • {Verifying circuits or methods}	11/4067 for memory cells of the bipolar type
11/2293	• • • {Timing circuits or methods}	11/407 for memory cells of the field-effect type 11/4072 Circuits for initialization, powering
11/2295	{Protection circuits or methods}	up or down, clearing memory or
11/2297	· · · · {Power supply circuits}	presetting
11/23	using electrostatic storage on a common	11/4074 Power supply or voltage generation
	layer, e.g. Forrester-Haeff tubes {or William tubes}(G11C 11/22 takes precedence)	circuits, e.g. bias voltage generators,
11/24	• using capacitors (G11C 11/22 takes precedence;	substrate voltage generators, back-up
11/2-	using a combination of semiconductor devices	power, power control circuits
	and capacitors <u>G11C 11/34</u> , e.g. <u>G11C 11/40</u>)	11/4076 Timing circuits (for regeneration
11/26	using discharge tubes	management <u>G11C 11/406</u>)
11/265	• • • {counting tubes, e.g. decatrons or trochotrons}	11/4078 Safety or protection circuits, e.g.
11/28	using gas-filled tubes	for preventing inadvertent or unauthorised reading or writing;
11/30	• • • using vacuum tubes (G11C 11/23 takes	Status cells; Test cells (protection of
	precedence)	memory contents during checking or
11/34	using semiconductor devices	testing <u>G11C 29/52</u>)
11/35	• • • with charge storage in a depletion layer, e.g.	11/408 Address circuits
11/26	charge coupled devices using diodes, e.g. as threshold elements	11/4082 {Address Buffers; level conversion
11/36	{, i.e. diodes assuming a stable ON-stage	circuits}
	when driven above their threshold (S- or N-	11/4085 {Word line control circuits, e.g.
	characteristic)}	word line drivers, - boosters, - pull- up, - pull-down, - precharge}
11/38	using tunnel diodes	11/4087 {Address decoders, e.g. bit - or
11/39	using thyristors {or the avalanche or negative	word line decoders; Multiple line
	resistance type, e.g. PNPN, SCR, SCS, UJT}	decoders}
11/40	using transistors	11/409 Read-write [R-W] circuits
11/401	forming cells needing refreshing or charge	11/4091 Sense or sense/refresh amplifiers,
11/400	regeneration, i.e. dynamic cells	or associated sense circuitry, e.g.
11/402	with charge regeneration individual to each memory cell, i.e. internal refresh	for coupled bit-line precharging,
11/4023	• • • • • {using field effect transistors}	equalising or isolating 11/4093 Input/output [I/O] data interface
11/4026	{using bipolar transistors}	arrangements, e.g. data buffers
11/403	• • • • with charge regeneration common to a	11/4094 Bit-line management or control
	multiplicity of memory cells, i.e. external	circuits
	refresh	11/4096 Input/output [I/O] data management
11/404	• • • • with one charge-transfer gate, e.g. MOS	or control circuits, e.g. reading or
44/4045	transistor, per cell	writing circuits, I/O drivers or bit-
11/4045	(using a plurality of serially	line switches
	connected access transistors, each having a storage capacitor}	11/4097 Bit-line organisation, e.g. bit-line layout, folded bit lines
11/405	• • • • • with three charge-transfer gates, e.g.	11/4099 Dummy cell treatment; Reference
11/105	MOS transistors, per cell	voltage generators
11/406	Management or control of the refreshing	11/41 forming {static} cells with positive feedback,
	or charge-regeneration cycles	i.e. cells not needing refreshing or charge
11/40603	• • • • • {Arbitration, priority and concurrent	regeneration, e.g. bistable multivibrator or
	access to memory cells for read/write or	Schmitt trigger
11/40/05	refresh operations}	11/411 using bipolar transistors only
11/40607	• • • • • {Refresh operations in memory devices with an internal cache or data buffer}	11/4113 {with at least one cell access to base
11/40611	• • • • • {External triggering or timing of	or collector of at least one of said transistors, e.g. via access diodes, access
11/70011	internal or partially internal refresh	transistors {
	operations, e.g. auto-refresh or CAS-	11/4116 {with at least one cell access via
	before-RAS triggered refresh}	separately connected emittors of said
11/40615		transistors or via multiple emittors, e.g.
	e.g. hidden refresh, self refresh, pseudo-	T2L, ECL}
	SRAMs}	11/412 using field-effect transistors only

	(2.11)	
11/4125	• • • • • {Cells incorporating circuit means for protecting against loss of information}	13/0014 • • • {comprising cells based on organic memory material}
11/413	• • • • Auxiliary circuits, e.g. for addressing,	13/0016 {comprising polymers}
	decoding, driving, writing, sensing, timing	13/0019 {comprising bio-molecules}
	or power reduction	13/0021 {Auxiliary circuits}
11/414	for memory cells of the bipolar type	13/0023 {Address circuits or decoders}
11/415	Address circuits	13/0026 {Bit-line or column circuits}
11/416	Read-write [R-W] circuits	13/0028 • • • • {Word-line or row circuits}
11/417	for memory cells of the field-effect type	13/003 {Cell access}
11/418	Address circuits	13/0033 • • • {Disturbance prevention or evaluation;
11/419	Read-write [R-W] circuits	Refreshing of disturbed memory data}
11/42	using opto-electronic devices, i.e. light-emitting and photoelectric devices electrically- or	13/0035 • • • {Evaluating degradation, retention or wearout, e.g. by counting writing cycles}
11/44	optically- coupled {or feedback-coupled}	13/0038 {Power supply circuits}
11/44	• using super-conductive elements, e.g. cryotron	13/004 {Reading or sensing circuits or methods}
11/46	• using thermoplastic elements	2013/0042 {Read using differential sensing, e.g. bit line
11/48	• using displaceable coupling elements, e.g.	[BL] and bit line bar [BLB]}
	ferromagnetic cores, to produce change between different states of mutual or self-inductance	2013/0045 {Read using current through the cell}
	{(contains no documents; see G11C 17/00 and	2013/0047 {Read destroying or disturbing the data}
	subgroups)}	2013/005 {Read using potential difference applied
11/50	 using actuation of electric contacts to store the 	between cell electrodes}
11/30	information	2013/0052 {Read process characterized by the shape,
11/52	using electromagnetic relays	e.g. form, length, amplitude of the read
11/54	 using elements simulating biological cells, e.g. 	pulse}
11/54	neuron	2013/0054 {Read is performed on a reference element,
11/56	• using storage elements with more than two stable	e.g. cell, and the reference sensed value is used to compare the sensed value of the
	states represented by steps, e.g. of voltage, current,	selected cell}
	phase, frequency	2013/0057 {Read done in two steps, e.g. wherein the
11/5607	• {using magnetic storage elements}	cell is read twice and one of the two read
11/5614	• • {using conductive bridging RAM [CBRAM] or	values serving as a reference value}
	programming metallization cells [PMC]}	13/0059 {Security or protection circuits or methods}
11/5621	• • {using charge storage in a floating gate}	13/0061 {Timing circuits or methods}
11/5628	• • • {Programming or writing circuits; Data input	13/0064 {Verifying circuits or methods}
	circuits}	2013/0066 {Verify correct writing whilst writing is in
11/5635	• • • {Erasing circuits}	progress, e.g. by detecting onset or cessation
11/5642	{Sensing or reading circuits; Data output	of current flow in cell and using the detector
	circuits}	output to terminate writing}
11/565	 {using capacitive charge storage elements} 	13/0069 {Writing or programming circuits or methods}
11/5657	• • {using ferroelectric storage elements}	2013/0071 {Write using write potential applied to access
11/5664	 {using organic memory material storage 	device gate}
	elements}	2013/0073 • • • • {Write using bi-directional cell biasing}
11/5671	• • {using charge trapping in an insulator}	2013/0076 {Write operation performed depending on
11/5678	• • {using amorphous/crystalline phase transition	read result}
	storage elements}	2013/0078 {Write using current through the cell}
11/5685	• • {using storage elements comprising metal oxide	2013/008 {Write by generating heat in the
	memory material, e.g. perovskites}	surroundings of the memory material, e.g.
11/5692	• • {read-only digital stores using storage elements	thermowrite}
	with more than two stable states}	2013/0083 {Write to perform initialising, forming
13/00	Digital stores characterised by the use of storage	process, electro forming or conditioning}
	elements not covered by groups G11C 11/00,	2013/0085 {Write a page or sector of information
	G11C 23/00, or G11C 25/00	simultaneously, e.g. a complete row or word
13/0002	• {using resistive RAM [RRAM] elements}	line}
13/0004	• • {comprising amorphous/crystalline phase	2013/0088 {Write with the simultaneous writing of a
	transition cells}	plurality of cells} 2013/009 • • • {Write using potential difference applied
13/0007	• • {comprising metal oxide memory material, e.g.	between cell electrodes}
	perovskites}	2013/0092 • • • {Write characterized by the shape, e.g. form
13/0009	{RRAM elements whose operation depends upon	length, amplitude of the write pulse}
	chemical change}	2013/0095 • • • {Write using strain induced by, e.g.
13/0011	• • • {comprising conductive bridging RAM	piezoelectric, thermal effects}
	[CBRAM] or programming metallization cells	13/0097 • • • {Erasing, e.g. resetting, circuits or methods}
	[PMCs]}	(Ziaong, e.g. recently, enemie of methods)

13/02	 using elements whose operation depends upon chemical change {(G11C 13/0009 takes 	16/0408	• • • {comprising cells containing floating gate transistors (G11C 16/0483, G11C 16/0491 take
	precedence)}		precedence)}
13/025	• • {using fullerenes, e.g. C60, or nanotubes, e.g. carbon or silicon nanotubes}	16/0416	• • • • {comprising cells containing a single floating gate transistor and no select transistor, e.g.
13/04	 using optical elements {; using other beam accessed elements, e.g. electron or ion beam} 	16/0425	UV EPROM} {comprising cells containing a merged
13/041	• • {using photochromic storage elements		floating gate and select transistor}
13/042	 (G11C 13/042 takes precedence)} • {using information stored in the form of interference pattern} 	16/0433	 {comprising cells containing a single floating gate transistor and one or more separate select transistors}
13/043	• • {using magnetic-optical storage elements}	16/0441	• • • {comprising cells containing multiple
		10/0441	floating gate devices, e.g. separate read-and-
13/044	• • { using electro-optical elements }		write FAMOS transistors with connected
13/045	• • { using photochromic storage elements }		
13/046	 • (using other storage elements storing information in the form of an interference pattern) 	16/045	floating gates} {Floating gate memory cells with both P and N channel memory transistors, usually
13/047	• • {using electro-optical elements (G11C 13/042		sharing a common floating gate}
	takes precedence)}	16/0458	• • • • {comprising two or more independent
13/048	• {using other optical storage elements}		floating gates which store independent
			data}
13/06	• using magneto-optical elements {(G11C 13/042	16/0466	• • • {comprising cells with charge storage in an
	takes precedence)}	10/0400	insulating layer, e.g. metal-nitride-oxide-silicon
14/00	D'. '4-1 - 4 1 4 - 2 1 b 4 - 2		
14/00	Digital stores characterised by arrangements		[MNOS], silicon-oxide-nitride-oxide-silicon
	of cells having volatile and non-volatile storage		[SONOS] (<u>G11C 16/0483</u> , <u>G11C 16/0491</u> take
	properties for back-up when the power is down		precedence)}
14/0009	• {in which the volatile element is a DRAM cell}	16/0475	• • • {comprising two or more independent
14/0018	• • {whereby the nonvolatile element is an EEPROM		storage sites which store independent data}
	element, e.g. a floating gate or metal-nitride-	16/0483	• • • {comprising cells having several storage
	oxide-silicon [MNOS] transistor}		transistors connected in series}
14/0027	• • {and the nonvolatile element is a ferroelectric	16/0491	• • • {Virtual ground arrays}
14/0027	element}	16/06	Auxiliary circuits, e.g. for writing into memory
14/0026			
14/0036	• • {and the nonvolatile element is a magnetic RAM	16/08	Address circuits; Decoders; Word-line control
4.4/00.4.7	[MRAM] element or ferromagnetic cell}		circuits
14/0045	• • {and the nonvolatile element is a resistive RAM	16/10	• • • Programming or data input circuits
	element, i.e. programmable resistors, e.g. formed	16/102	• • • {External programming circuits, e.g.
	of phase change or chalcogenide material}		EPROM programmers; In-circuit
14/0054	• {in which the volatile element is a SRAM cell}		programming or reprogramming; EPROM
14/0063	• • {and the nonvolatile element is an EEPROM		emulators}
	element, e.g. a floating gate or MNOS transistor}	16/105	• • • • {Circuits or methods for updating contents
14/0072	• • {and the nonvolatile element is a ferroelectric		of nonvolatile memory, especially with
	element}		'security' features to ensure reliable
14/0081	• • {and the nonvolatile element is a magnetic RAM		replacement, i.e. preventing that old data is
14/0001	[MRAM] element or ferromagnetic cell}		lost before new data is reliably written}
1.4/000		16/107	· · · · · · · · · · · · · · · · · · ·
14/009	• • {and the nonvolatile element is a resistive RAM	16/10/	• • • {Programming all cells in an array, sector or
	element, i.e. programmable resistors, e.g. formed		block to the same state prior to flash erasing}
	of phase change or chalcogenide material}	16/12	Programming voltage switching circuits
15/00	Digital stores in which information comprising	16/14	Circuits for erasing electrically, e.g. erase
13/00	one or more characteristic parts is written into		voltage switching circuits
		16/16	for erasing blocks, e.g. arrays, words,
	the store and in which information is read-out by		groups
	searching for one or more of these characteristic	16/18	Circuits for erasing optically
	parts, i.e. associative or content-addressed stores	16/20	Initialising; Data preset; Chip identification
15/02	 using magnetic elements 	16/22	Safety or protection circuits preventing
15/04	 using semiconductor elements 	10/22	
15/043	• • {using capacitive charge storage elements}		unauthorised or accidental access to memory
15/046	• • {using non-volatile storage elements}	16/225	cells
15/06	using cryogenic elements	16/225	• • • • {Preventing erasure, programming or reading
			when power supply voltages are outside the
16/00	Erasable programmable read-only memories		required ranges}
	(G11C 14/00 takes precedence)	16/24	Bit-line control circuits
16/02	electrically programmable	16/26	Sensing or reading circuits; Data output circuits
16/04	• using variable threshold transistors, e.g. FAMOS	16/28	using differential sensing or reference cells,
10/0 F	Some immore anomore amonomore, e.g. 1711100		e.g. dummy cells
		16/30	Power supply circuits
		10/30	

16/32	Timing circuits	16/3481	• • • • • {Circuits or methods to verify correct
16/34	Determination of programming status, e.g.		programming of nonvolatile memory
	threshold voltage, overprogramming or		cells whilst programming is in progress,
	underprogramming, retention		e.g. by detecting onset or cessation
16/3404	{Convergence or correction of memory cell		of current flow in cells and using
	threshold voltages; Repair or recovery of		the detector output to terminate
	overerased or overprogrammed cells}		programming}
16/3409	{Circuits or methods to recover overerased	16/3486	• • • • • {Circuits or methods to prevent
	nonvolatile memory cells detected during		overprogramming of nonvolatile
	erase verification, usually by means of a		memory cells, e.g. by detecting onset
	"soft" programming step}		or cessation of current flow in cells and
16/3413	{Circuits or methods to recover		using the detector output to terminate
	overprogrammed nonvolatile memory		programming}
	cells detected during program verification,	16/349	• • • {Arrangements for evaluating degradation,
	usually by means of a "soft" erasing step}		retention or wearout, e.g. by counting erase
16/3418	{Disturbance prevention or evaluation;		cycles}
10,0.10	Refreshing of disturbed memory data}	16/3495	{Circuits or methods to detect or delay
16/3422	{Circuits or methods to evaluate read or		wearout of nonvolatile EPROM or
10/3422	write disturbance in nonvolatile memory,		EEPROM memory devices, e.g. by
	without steps to mitigate the problem}		counting numbers of erase or reprogram
16/3427	{Circuits or methods to prevent or reduce		cycles, by using multiple memory areas
10/3427	disturbance of the state of a memory		serially or cyclically}
	cell when neighbouring cells are read or		
	written	17/00	Read-only memories programmable only once;
16/3431	,		Semi-permanent stores, e.g. manually-replaceable
16/3431	{Circuits or methods to detect disturbed		information cards
	nonvolatile memory cells, e.g. which still	17/005	• {with a storage element common to a large
	read as programmed but with threshold		number of data, e.g. perforated card (G11C 17/02,
	less than the program verify threshold or		G11C 17/04 take precedence)
	read as erased but with threshold greater	17/02	 using magnetic or inductive elements (G11C 17/14)
	than the erase verify threshold, and to		takes precedence)
	reverse the disturbance via a refreshing	17/04	• using capacitive elements (G11C 17/06,
1.5/0.405	programming or erasing step}		G11C 17/14 take precedence)
16/3436	{Arrangements for verifying correct	17/06	• using diode elements (G11C 17/14 takes
	programming or erasure}		precedence)
16/344	{Arrangements for verifying correct	17/08	• using semiconductor devices, e.g. bipolar elements
	erasure or for detecting overerased cells}		(G11C 17/06, G11C 17/14 take precedence)
16/3445	{Circuits or methods to verify correct	17/10	in which contents are determined during
	erasure of nonvolatile memory cells}		manufacturing by a predetermined arrangement
16/345	• • • • • {Circuits or methods to detect		of coupling elements, e.g. mask-programmable
	overerased nonvolatile memory cells,		ROM
	usually during erasure verification}	17/12	using field-effect devices
16/3454	• • • • {Arrangements for verifying correct	17/123	{comprising cells having several storage
	programming or for detecting	17/123	transistors connected in series}
	overprogrammed cells}	17/126	· · · · {Virtual ground arrays}
16/3459	• • • • • {Circuits or methods to verify correct	17/120	 in which contents are determined by selectively
	programming of nonvolatile memory	1 // 14	
	cells}		establishing, breaking or modifying connecting
16/3463	{Circuits or methods to detect		links by permanently altering the state of coupling
	overprogrammed nonvolatile memory	17/1/2	elements, e.g. PROM
	cells, usually during program	17/143	• • {using laser-fusible links}
	verification}	17/146	• • {Write once memory, i.e. allowing changing of
16/3468	{Prevention of overerasure or		memory content by writing additional bits}
	overprogramming, e.g. by verifying whilst	17/16	 using electrically-fusible links
	erasing or writing}	17/165	{Memory cells which are electrically
16/3472	{Circuits or methods to verify correct		programmed to cause a change in resistance,
10/31/2	erasure of nonvolatile memory cells		e.g. to permit multiple resistance steps to be
	whilst erasing is in progress, e.g. by		programmed rather than conduct to or from
	detecting onset or cessation of current		non-conduct change of fuses and antifuses
	flow in cells and using the detector		(digital stores using resistance random access
	output to terminate erasure}		memory elements G11C 13/0002)}
16/3477	· · · · · {Circuits or methods to prevent	17/18	Auxiliary circuits, e.g. for writing into memory
10/J-T//	overerasing of nonvolatile memory	10/00	Distributions in subtribute to form of
	cells, e.g. by detecting onset or cessation	19/00	Digital stores in which the information is moved
	of current flow in cells and using the	10/00=	stepwise, e.g. shift registers
	detector output to terminate erasing}	19/005	• {with ferro-electric elements (condensers)}
	detector darpar to terminate erasing)		

19/02	 using magnetic elements (G11C 19/14 takes precedence) 	19/30	 using opto-electronic devices, i.e. light-emitting and photoelectric devices electrically- or optically-
19/04	using cores with one aperture or magnetic loop		coupled
19/06	 using structures with a number of apertures or 	19/32	 using super-conductive elements
17/00	magnetic loops, e.g. transfluxors {laddic}	19/34	 using storage elements with more than two stable
19/08	 using thin films in plane structure 	17/54	states represented by steps, e.g. of voltage, current,
19/0808	using thin finits in plane structureusing magnetic domain propagation}		phase, frequency
		19/36	• using {multistable} semiconductor elements
19/0816	• • • {using a rotating or alternating coplanar	19/38	 two-dimensional, e.g. horizontal and vertical shift
40,000	magnetic field}	19/30	
19/0825	• • • {using a variable perpendicular magnetic		registers
	field}	21/00	Digital stores in which the information circulates
19/0833	• • • {using magnetic domain interaction}		{continuously}(stepwise G11C 19/00)
19/0841	• • • {using electric current}	21/005	• {using electrical delay lines}
19/085	• • • {Generating magnetic fields therefor, e.g.	21/02	 using electromechanical delay lines, e.g. using a
	uniform magnetic field for magnetic domain	21/02	mercury tank
	stabilisation}	21/023	
19/0858	• • • {Generating, replicating or annihilating	21/023	tank}
	magnetic domains (also comprising different	21/026	,
	types of magnetic domains, e.g. "Hard	21/026	• • {using magnetostriction transducers, e.g. nickel
	Bubbles") (G11C 19/0866 takes precedence)}		delay line}
19/0866	{Detecting magnetic domains}	23/00	Digital stores characterised by movement of
19/0875	• • • (Organisation of a plurality of magnetic shift	20,00	mechanical parts to effect storage, e.g. using balls;
15/00/5	registers}		Storage elements therefor
19/0883	• • • {Means for switching magnetic domains		Storage elements therefor
17/0003	from one path into another path, i.e. transfer	25/00	Digital stores characterised by the use of flowing
	switches, swap gates or decoders}		media; Storage elements therefor
10/0001	* *	2=100	
19/0891	• • • • {using hybrid structure, e.g. ion doped	27/00	Electric analogue stores, e.g. for storing
10/10	layers}		instantaneous values
19/10	• using thin films on rods; with twistors	27/005	• {with non-volatile charge storage, e.g. on floating
19/12	. using non-linear reactive devices in resonant circuits		gate or MNOS}
	{, e.g. parametrons; magnetic amplifiers with	27/02	 Sample-and-hold arrangements (G11C 27/04 takes
	overcritical feedback}		precedence)
19/14	 using magnetic elements in combination with active 	27/022	• {using a magnetic memory element}
	elements, e.g. discharge tubes, semiconductor	27/024	• • {using a capacitive memory element (G11C 27/04
	elements {(contains no documents, see provisionally		takes precedence)}
	<u>G11C 19/02</u> - <u>G11C 19/10</u>)}	27/026	• • • {associated with an amplifier (G11C 27/028
19/18	• using capacitors as main elements of the stages {(if		takes precedence)}
	capacitors are used as auxiliary stage in between	27/028	• • • {Current mode circuits, e.g. switched current
	main stages with other elements, the latter take	277020	memories}
	precedence; G11C 19/005 takes precedence)	27/04	Shift registers
19/182	• • {in combination with semiconductor elements,	27/04	• billit registers
	e.g. bipolar transistors, diodes}	29/00	Checking stores for correct operation {;
19/184	• • { with field-effect transistors, e.g. MOS-FET}		Subsequent repair}; Testing stores during standby
19/186	• • • {using only one transistor per capacitor, e.g.		or offline operation
19/100	bucket brigade shift register}	29/003	• {in serial memories}
10/100	{Organisation of a multiplicity of shift	29/006	• {at wafer scale level, i.e. wafer scale integration
19/188		25/000	[WSI]}
	registers, e.g. regeneration, timing or input-	29/02	 Detection or location of defective auxiliary circuits,
10/20	output circuits}	27/02	e.g. defective refresh counters
19/20	• using discharge tubes (G11C 19/14 takes	20/021	-
	precedence)	29/021	• • {in voltage or current generators}
19/202	• • {with vacuum tubes (<u>G11C 19/207</u> takes	29/022	• • {in I/O circuitry}
	precedence)}	29/023	• • {in clock generator or timing circuitry}
19/205	• • {with gas-filled tubes (<u>G11C 19/207</u> takes	29/024	• • {in decoders}
	precedence)}	29/025	• • {in signal lines}
19/207	• • {with counting tubes}	29/026	• • {in sense amplifiers}
19/28	• using semiconductor elements (G11C 19/14,	29/027	• • {in fuses}
	G11C 19/36 take precedence)	29/028	• • {with adaption or trimming of parameters}
19/282	• • {with charge storage in a depletion layer, i.e.	29/04	Detection or location of defective memory elements
	charge coupled devices [CCD]}	27/04	{, e.g. cell constructio details, timing of test signals}
19/285	• • • {Peripheral circuits, e.g. for writing into the	2020/0401	
171200	first stage; for reading-out of the last stage}	2029/0401	• • {in embedded memories}
19/287	• {Organisation of a multiplicity of shift registers}	2029/0403	• . {during or with feedback to manufacture}
19/20/	• • {Organisation of a muniplicity of sinit registers}	2029/0405	• • {comprising complete test loop}
		2029/0407	• • {on power on}
		2029/0409	• • {Online test}

2029/0411 • • {Online error correction}	29/50004 { of threshold voltage }
29/06 Acceleration testing	29/50008 • • • {of impedance}
29/08 • Functional testing, e.g. testing during refresh,	29/50012 {of timing}
power-on self testing [POST] or distributed	29/50016 {of retention}
testing	
29/10 Test algorithms, e.g. memory scan [MScan]	2029/5002 {Characteristic}
algorithms; Test patterns, e.g. checkerboard	2029/5004 {Voltage}
patterns	2029/5006 {Current}
29/12 Built-in arrangements for testing, e.g. built-in	29/52 • Protection of memory contents; Detection of errors
self testing [BIST] {or interconnection details}	in memory contents
9 \	29/54 • Arrangements for designing test circuits, e.g. design
29/12005 {comprising voltage or current generators}	for test [DFT] tools
29/1201 {comprising I/O circuitry}	29/56 • External testing equipment for static stores, e.g.
29/12015 {comprising clock generation or timing	automatic test equipment [ATE]; Interfaces therefor
circuitry}	29/56004 {Pattern generation}
2029/1202 {Word line control}	29/56008 {Error analysis, representation of errors}
2029/1204 • • • • {Bit line control}	29/56012 {Timing aspects, clock generation,
2029/1206 • • • • {Location of test circuitry on chip or wafer}	synchronisation}
2029/1208 • • • • {Error catch memory}	29/56016 • • {Apparatus features}
29/14 Implementation of control logic, e.g. test	2029/5602 • • {Interface to device under test}
mode decoders	2029/5604 {Display of error information}
29/16 using microprogrammed units, e.g. state	
machines	2,7
29/18 Address generation devices; Devices	• {Masking faults in memories by using spares or by
for accessing memories, e.g. details of	reconfiguring}
addressing circuits	29/702 • • {by replacing auxiliary circuits, e.g. spare voltage
2029/1802 {Address decoder}	generators, decoders or sense amplifiers, to be
	used instead of defective ones}
,	29/72 • • { with optimized replacement algorithms }
2029/1806 {Address conversion or mapping, i.e.	29/74 {using duplex memories, i.e. using dual copies}
logical to physical address}	29/76 • • {using address translation or modifications}
29/20 using counters or linear-feedback shift	29/765 {in solid state disks}
registers [LFSR]	29/78 {using programmable devices}
29/22 Accessing serial memories	29/781 {combined in a redundant decoder}
29/24 Accessing extra cells, e.g. dummy cells or	29/783 • • • { with refresh of replacement cells, e.g. in
redundant cells	DRAMs}
29/26 Accessing multiple arrays (G11C 29/24	29/785 {with redundancy programming schemes}
takes precedence)	29/787 {using a fuse hierarchy}
2029/2602 {Concurrent test}	29/789 {using a ruse increasing}
29/28 Dependent multiple arrays, e.g. multi-bit	· · ·
arrays	29/80 {with improved layout}
29/30 Accessing single arrays	29/802 {by encoding redundancy signals}
29/32 Serial access; Scan testing	29/804 {to prevent clustered faults}
2029/3202 {Scan chain}	29/806 {by reducing size of decoders}
29/34 Accessing multiple bits simultaneously	29/808 {using a flexible replacement scheme}
29/36 Data generation devices, e.g. data inverters	29/81 {using a hierarchical redundancy scheme}
2029/3602 {Pattern generator}	29/812 {using a reduced amount of fuses}
	29/814 {for optimized yield}
29/38 Response verification devices	29/816 {for an application-specific layout}
29/40 using compression techniques	29/818 {for dual-port memories}
2029/4002 {Comparison of products, i.e. test results	29/82 {for EEPROMs}
of chips or with golden chip}	29/822 {for read only memories}
29/42 using error correcting codes [ECC] or	
parity check	29/824 {for synchronous memories}
29/44 Indication or identification of errors, e.g. for	29/83 {with reduced power consumption}
repair	29/832 { with disconnection of faulty elements}
29/4401 { for self repair }	29/835 { with roll call arrangements for redundant
2029/4402 {Internal storage of test result, quality data,	substitutions}
chip identification, repair information}	29/838 {with substitution of defective spares}
29/46 Test trigger logic	29/84 • • • {with improved access time or stability}
29/48 Arrangements in static stores specially adapted	29/842 {by introducing a delay in a signal path}
for testing by means external to the store, e.g.	29/844 {by splitting the decoders in stages}
using direct memory access [DMA] or using	29/846 {by choosing redundant lines at an output
auxiliary access paths	stage}
29/50 . Marginal testing, e.g. race, voltage or current	29/848 {by adjacent switching}
testing	(· J · · · · · · · · · · · · · · · · ·
S	

29/86	 {in serial access memories, e.g. shift registers, CCDs, bubble memories} 	2211/4013 Memory devices with multiple cells per bit, e.g. twin-cells
29/88	• • {with partially good memories}	2211/4016 • • Memory devices with silicon-on-insulator cells
29/883	• • • {using a single defective memory device with	2211/406 • Refreshing of dynamic cells
	reduced capacity, e.g. half capacity}	2211/4061 Calibration or ate or cycle tuning
29/886	{combining plural defective memory devices	2211/4062 Parity or ECC in refresh operations
	to provide a contiguous address range, e.g.	2211/4063 Interleaved refresh operations
	one device supplies working blocks to replace	2211/4065 Low level details of refresh operations
	defective blocks in another device}	2211/4066 Pseudo-SRAMs
99/00	Subject matter not provided for in other groups of	2211/4067 Refresh in standby or low power modes
	this subclass	2211/4068 Voltage or leakage in refresh operations
		2211/56 • Indexing scheme relating to G11C 11/56 and sub-
2207/00	Indexing scheme relating to arrangements for	groups for features not covered by these groups
	writing information into, or reading information out from, a digital store	2211/561 Multilevel memory cell aspects
2207/002		2211/5611 Multilevel memory cell with more than one
2207/002	Isolation gates, i.e. gates coupling bit lines to the sense amplifier	control gate
2207/005	Transfer gates, i.e. gates coupling the sense	2211/5612 Multilevel memory cell with more than one
2207/003	amplifier output to data lines, I/O lines or global bit	floating gate
	lines	2211/5613 Multilevel memory cell with additional gates, not being floating or control gates
2207/007	Register arrays	2211/5614 Multilevel memory cell comprising negative
2207/06	Sense amplifier related aspects	resistance, quantum tunneling or resonance
2207/061	Sense amplifier enabled by a address transition	tunneling elements
	detection related control signal	2211/5615 Multilevel magnetic memory cell using non-
2207/063	Current sense amplifiers	magnetic non-conducting interlayer, e.g. MTJ
2207/065	Sense amplifier drivers	2211/5616 Multilevel magnetic memory cell using non-
2207/066	Frequency reading type sense amplifier	magnetic conducting interlayer, e.g. GMR, SV,
2207/068	Integrator type sense amplifier	PSV
2207/10	Aspects relating to interfaces of memory device to	2211/5617 Multilevel ROM cell programmed by source,
	external buses	drain or gate contacting
2207/101	Analog or multilevel bus	2211/562 Multilevel memory programming aspects
2207/102	Compression or decompression of data before	2211/5621 Multilevel programming verification
	storage	2211/5622 Concurrent multilevel programming of more
2207/104	. Embedded memory devices, e.g. memories with	than one cell
	a processing device on the same die or ASIC memory designs	2211/5623 Concurrent multilevel programming and reading
2207/105	Aspects related to pads, pins or terminals	2211/5624 Concurrent multilevel programming and
2207/103	Serial-parallel conversion of data or prefetch	programming verification
2207/107	. Wide data ports	2211/5625 Self-converging multilevel programming
2207/100	Equalization of bit lines	2211/563 • Multilevel memory reading aspects
2207/16	Solid state audio (deprecated, only for historical	2211/5631 Concurrent multilevel reading of more than one
2207/10	reasons, <u>G06F 3/16</u> , <u>G11B</u>)	cell
2207/22	Control and timing of internal memory operations	2211/5632 Multilevel reading using successive
2207/2209	Concurrent read and write (for multi-port memory	approximation
	<u>G11C 7/1075</u>)	2211/5633 Mixed concurrent serial multilevel reading
2207/2218	Late write	2211/5634 Reference cells
2207/2227	Standby or low power modes	2211/564 • Miscellaneous aspects
2207/2236	Copy	2211/5641 Multilevel memory having cells with different
2207/2245	Memory devices with an internal cache buffer	number of storage levels
2207/2254	Calibration	2211/5642 Multilevel memory with buffers, latches,
2207/2263	• Write conditionally, e.g. only if new data and old	registers at input or output
	data differ	2211/5643 Multilevel memory comprising cache storage devices
2207/2272	Latency related aspects	
2207/2281	. Timing of a read operation (sense amplifier timing G11C 7/06, G11C 7/08)	2211/5644 Multilevel memory comprising counting devices
2207/229	Timing of a write operation (sense amplifier)	2211/5645 Multilevel memory with current-mirror
22011227	timing G11C 7/06, G11C 7/08)	arrangements
		2211/5646 Multilevel memory with flag bits, e.g. for
2211/00	Indexing scheme relating to digital stores	showing that a "first page" of a word line is
	characterized by the use of particular electric	programmed but not a "second page"
	or magnetic storage elements; Storage elements therefor	2211/5647 Multilevel memory with bit inversion
2211/401	Indexing scheme relating to cells needing refreshing	arrangement
2211/ 4 01	or charge regeneration, i.e. dynamic cells	

or charge regeneration, i.e. dynamic cells

2213/09 Indexing scheme relating to C11C 1300 for features not covered by this group? 2213/10 Indexing scheme relating to C11C 1300 for features not covered by this group? 2213/11 Meanilor Implying, i.e., using memory material temperatures of the material of the memory active layer in redox material trapping i.e., using memory material temperatures of the material trapping i.e., using memory material temperatures of the material trapping income the relation is combe trapped but do not meat and form an electrode deposit creating flaments or dendrities of the material trapping non-metal ions given by the electrode or another layer during a write operation, are dissociated in ions which migrate operation, are dissociated in ions which migrate operation, are dissociated in ions which migrate operation, are dissociated in fone which migrate operation are dissociated i	2211/5648	• • • Multilevel memory programming, reading or erasing operations wherein the order or sequence of the operations is relevant	2213/56	Structure including two electrodes, a memory active layer and a so called passive or source or reservoir layer which is NOT an electrode,
2213/0 Indexing scheme relating to GIIC 1300 for features not covered by this group 2213/10 . Resistive cells: Technology aspects 2213/11 . Meat lon trapping, i.e. using memory material including cavities, pores or spaces in form of tunnels or channels wherein metal ions can be trapped but do not react and form un electrode posit creating filaments or dendrites 2213/72 . Non-metal ion trapping, i.e. using memory material representation of the position of the propertion of the propertion of the position of	2211/5649	in order to lower programming voltages		
2213/10 Indexing scheme relating to GHC 1500 for features not overee by this group 2213/10 Resistive cells; Technology aspects 2213/11 The dimensional array 2213/12 Induced or channels wherein metal ions can be trapped but do not react and form an electrode posit creating filaments or deadnities 2213/13 Array wherein the access device being a dinde function deposit creating filaments or deadnities 2213/13 Array wherein the access device being a dinde function deposit creating filaments or deadnities 2213/13 Array wherein the access device being a dinde function deposit creating filaments or deadnities 2213/13 Array wherein the access device being used function. Being merged with memorizing function of memory cells memory cell has more than one access device function. Being merged with memorizing function of memory cells in series or memory cell mindthing molecules which, during a write operation, are dissociated in ions which migrate turber in the memory material relating to pertainty. Being a manowire and the control of the memory cell in a partial to different molecule structures as storage states, e.g. part of molecule being a partial relation of memory cell being a manowire having RADIA1 composition of Memory cell being a nanowire having RADIA1 composition of where the memory elements in series, a memory decell which being not a transistor and tot a diode transition of all you terminals and used to the composition of memory cells of a group share and any access device being used Array wherein the memory cells of the group having a common electrode and the access device being used and a conditions of the memory cells of the group having a common electrode and the access device being used and a conditions of the manory and the access device being used and a conditions of the manory and the access device being used and a conditions of the manory cells of the group having a common electrode and the access device being used and a conditions of the proposition of the manory cells of the group having a common elec	2211/565			form conductive filaments there or to react with
2213/10 . Resistive early spects 2213/11 . Resistive army spects 2213/11 . Metal ion trapping, i.e. using memory material including earlytics, porces or spaces in form of tunnels or channels wherein metal ions can be trapped but do not react and form an electro-deposit creating filaments or dendrities 2213/12 . Non-metal ion trapping, i.e. using memory material trapping non-metal ions given by the electrode or another layer during a write operation, e.g. trapping, doping 2213/13 . Dissociation, i.e. using memory material including molecules which, during a write operation, are dissociated in ions which imjerate further in the memory material including molecules which, during a write operation, are dissociated in ions which imjerate further in the memory material trapped curve. 2213/14 . Wes of different molecule being rotated 2213/15 . Current-voltage curve 2213/16 . Memory cell being a nanotive, e.g. suspended nanotube 2213/17 . Memory cell being a nanotive nanotive ananotive ananotive ananotive ananotive composition only two terminals 2213/19 . Memory cell being a nanowire having RADIAL composition only two terminals 2213/19 . Memory cell being a nanowire having RADIAL composition only two terminals 2213/31 . Material including silicon 2213/32 . Material including silicon 2213/33 . Material including silicon 2213/34 . Material including silicon 2213/35 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode attracture 2213/35 . Structure wherein the resistive material being in a transistor, e.g. garbite, graphene 2213/35 . Structure wherein the resistive material being in a transistor, e.g. garbite, graphene 2213/35 . Structure wherein the resistive material being in a transistor, e.g. garbite, graphene 2213/35 . Structure wherein the resistive material being in a transistor, e.g. garbite, graphene 2213/35 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/35 . Structure wherein the resist	2213/00	Indexing scheme relating to G11C 13/00 for		
2213/10 - Resistive cells; Technology aspects whether the control of tunnels or chamels wherein metal ions can be trapped but do not react and form an electrodeposit creating filaments or dendrites wherein metal ions can be trapped but do not react and form an electrodeposit creating filaments or dendrites wherein metal ions can be trapped but do not react and form an electrodeposit creating filaments or dendrites wherein metal ions can be trapped but do not react and form an electrodeposit creating incorrect in large during a write operation, are grapping, doping non-metal ions given by the electrode are another layer during a write operation, are dissociated in lons which migrate further in the memory material including molecules which, during a write operation, are dissociated in lons which migrate further in the memory tell molecules which during a write operation, are dissociated in lons which migrate further in the memory cell of molecules being rotated states, e.g. part of molecule being rotated states, e.g. part of molecule being rotated which being a nation with a memory cell pering a manotube, e.g. suspended nanotube and monly two terminals. Memory cell being a nanowire transistor composition which will be memory cells of a group share an access device being used word lines without any access device being need with the memory cells of a group share an access device being a directly connected to the hill insa and office of th		features not covered by this group	2213/70	
2213/12 . Metal ion trapping, ic. using memory material including earlies, prores or spaties, prores or spaties, processor spat	2213/10	Resistive cells; Technology aspects		
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deposit creating filaments of dendrites Non-metal ton trapping, i.e. using memory material trapping anon-metal ions given by the electrode or another layer during a write operation, e.g. trapping, doping 2213/13		tunnels or channels wherein metal ions can be	2213/73	Array where access device function, e.g. diode function, being merged with memorizing function
nearesit trapping non-metal toos given by the electrode or another layer during a write operation, e.g. trapping, doping and charged through a write operation, are dissociated in toos which migrate further in the memory material including molecules which, during a write operation, are dissociated in toos which migrate further in the memory material 2213/14 . Use of different molecule structures as storage states, e.g. part of molecule being rotated states, e.g. part of molecule being rotated annotable with annotable anno			2212/74	
material trappling non-metal ions given by the electrode or another layer during a write operation, e.g. trapping, doping 2213/13	2213/12		2213/74	
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2213/13 - Dissociation, i.e. using memory material including molecules which, during a write operation, are dissociated in lons which thirgrate further in the memory material including molecules which, during a write operation, are dissociated in lons which migrate further in the memory material operation, and expert of molecule being rotated 2213/15 - Current-voltage curve 2213/16 - Memory cell being a nanowire transistor 2213/18 - Memory cell being a nanowire transistor 2213/18 - Memory cell being a nanowire transistor 2213/19 - Memory cell being a nanowire having RADIAL composition 2213/19 - Memory cell comprising at least a nanowire and only two terminals 2213/30 - Resistive cell, memory material aspects 2213/31 - Material including arbon, e.g. graphite, grapheme 2213/32 - Material including arbon, e.g. graphite, grapheme 2213/35 - Structure including a harrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode attransistor e.g. gate 2213/55 - Structure including a tunneling barrier layer, the memory cell growing an access device for each cell which being an access device for each cell which being an access device for each cell which being an access device to five their group salvare an access device being a transistor and or a diode connected to the bit lines and word line and research the memory cells of the group having a common electrode and the access device being an opart of a word line or a bit line driver 2213/78 - Array wherein the substrate, the cell, the conductors and the access device being an opart of a word line or a bit line driver 2213/78 - Array wherein the substrate, the cell, the conductors and the access device being an opart of a word line, a bit line, and a part of a word line, a bit line and a part or adverse device being an opart of a word line or a bit line driver 213/780 - Array wherein the substrate, the cell, the conductors and the access device being an anowine the group have an access device. In the group have of		the electrode or another layer during a write	2213/73	
2213/14 . Use of different molecules which, during a write operation, are dissociated in ions which migrate further in the memory material states, e.g. part of molecule being rotated states, e.g. part of molecule being rotated annotube manotube in gananowire transistor annotube annotube annotube in gananowire transistor annotube ann		operation, e.g. trapping, doping		
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poperation, are dissociated in ions which migrate further in the memory material 2213/14 . Use of different molecule structures as storage states, e.g. part of molecule being rotated 2213/16 . Memory cell being a nanotube, e.g. suspended nanotube in anotube in gan anowire transistor 2213/17 . Memory cell being a nanowire transistor 2213/18 . Memory cell being a nanowire having RADIAL composition only two terminals only the terminal transition only two terminals only two terminals only the provision of the memory tells of a group share an access device being an ac			2213/76	
2213/14 Use of different molecule structures as storage states, e.g. part of molecule being rotated 2213/15 Current-voltage curve 2213/16 . Memory cell being a nanotube 2213/17 Memory cell being a nanowire transistor 2213/18 Memory cell being a nanowire having RADIAL composition 2213/19 . Memory cell being a nanowire having RADIAL composition 2213/20 . Memory cell comprising at least a nanowire and only two terminals only two terminals 2213/31 Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material having simple binary metal oxide perovskite structure 2213/33 Material includes an oxide or a nitride 2213/35 . Material including silicon 2213/36 . Material including silicon 2213/37 Material including carbon, e.g. graphite, grapheme 2213/37 Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/35 Structure wherein the resistive material being in a transistor, e.g. gate 2213/35 Structure wherein the resistive material being in a transistor, e.g. gate 2213/35 Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/36 Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/36 Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2213/55 Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/16 Structure including two electrodes, a memory active layer or a less doped memory active layer 2216/16 Floating gate cells in which the floating gate consists of multiple isolated silicon islands, e.g. nanocrystale memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. sin			2213/70	
2213/14 • . Use of different molecule structures as storage states, e.g. part of molecule being rotated 2213/15 • . Current-voltage curve 2213/16 • . Memory cell being a nanotube, e.g. suspended nanotube 2213/17 • . Memory cell being a nanowire transistor 2213/18 • . Memory cell being a nanowire having RADIAL composition 2213/19 • . Memory cell comprising at least a nanowire and only two terminals 2213/30 • . Resistive cell, memory material aspects 2213/31 • . Material having complex metal oxide, e.g. perovskite structure 2213/32 • . Material having complex metal oxide structure 2213/33 • . Material including silicon structure 2213/34 • . Material including carbon, e.g. graphite, grapheme 2213/35 • . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation or electrolytes near an electrode 2213/52 • . Structure characterized by the electrode material, shape, etc. 2213/53 • . Structure herein the resistive material being in a transistor, e.g. gate 2213/54 • . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 • . Structure herein the resistive material being in a transistor, e.g. gate 2213/55 • . Structure including tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 • . Structure including tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 • . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2213/56 • . Structure including tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/56 • . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2213/56 • . Structure including a tunne			2213/77	
2213/15 . Current-voltage curve 2213/16 . Memory cell being a nanotube 2213/17 . Memory cell being a nanowire transistor 2213/18 . Memory cell being a nanowire having RADIAL composition 2213/19 . Memory cell comprising at least a nanowire and only two terminals 2213/30 . Resistive cell, memory material aspects 2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material having complex metal oxide structure 2213/33 . Material including silicon 2213/35 . Material including silicon 2213/36 . Material including a barrier layer grapheme 2213/37 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/54 . Structure including a unneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer che memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer or a less doped memory active layer 2213/56 . Structure including a tunneling barrier layer or a less doped memory active layer 2213/56 . Structure including a tunneling barrier layer or a less doped memory active layer 2213/56 . Structure including a tunneling barrier layer or a less doped memory active layer 2213/56 . Structure including a tunneling barrier layer or a less doped memory active layer 2213/57 . Structure including a tunneling barrier layer. 2213/58 . Structure including a tunneling barrier layer. 2213/59 . Structure including a tunneling barrier layer. 2213/50 . Structure including a tunneling barrier layer. 2213/50 . Structure including a tunneling barrier layer. 2213/50 . Structure including a tunneling barrier	2213/14		2213///	
2213/15 . Current-voltage curve 2213/16 . Memory cell being a nanotube, e.g. suspended anotube 2213/17 . Memory cell being a nanowire transistor 2213/18 . Memory cell being a nanowire transistor 2213/19 . Memory cell comprising at least a nanowire and only two terminals 2213/30 . Resistive cell, memory material aspects 2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material having complex metal oxide structure 2213/33 . Material includes an oxide or a nitride 2213/35 . Material includes an oxide or a nitride 2213/35 . Material including silicon 2213/36 . Structure including a barrier layer preventing or formation of electrolytes near an electrode 2213/51 . Structure characterized by the electrode material, shape, etc. 2213/52 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including tumneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2213/56 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 . Nonvolatile memory wherein that enemory cells of the group share an ancexes device being a transistor. 2216/10 . Array wherein the memory cells of the group share an ancexes device being a transistor. 2213/81 . Array wherein the memory sells of the access device being a transistor. 2213/82 . Array subrein: the ememory sell made up of organic materials 2216/00 . Array wherein the memory sells of the arcaes				
2213/16 • Memory cell being a nanotube, e.g. suspended nanotube 2213/17 • Memory cell being a nanowire transistor 2213/18 • Memory cell being a nanowire transistor 2213/19 • Memory cell comprising at least a nanowire and only two terminals 2213/20 • Resistive cell, memory material aspects 2213/31 • Material having complex metal oxide, e.g. perovskite structure 2213/32 • Material having simple binary metal oxide structure 2213/34 • Material including silicon 2213/35 • Material including silicon 2213/36 • Resistive cell structure aspects 2213/37 • Material including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 • Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/53 • Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 • Structure wherein the resistive material being in a transistor, e.g. gate 2213/55 • Structure including a tunneling barrier layer, the memory effect implying the modification of unnel barrier conductivity 2213/55 • Structure including wood electrodes, a memory aless doped memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 • Structure including two electrodes, a memory effect implying the modification of unnel barrier conductivity 2216/10 • Floating gate memory eells with a single polysilicon layer 2216/10 • Floating gate memory ells with a single polysilicon layer 2216/10 • Floating gate memory cells with a single polysilicon insultaneously into a nonvolatile memory, typically a complete row or word line in flash memory 2216/16 • Floating gate memory of all the cells in an array,			2213/78	
2213/17	2213/16	· · · · · · · · · · · · · · · · · · ·		
2213/18				group having a common electrode and the access
composition 2213/19 . Memory cell comprising at least a nanowire and only two terminals 2213/30 . Resistive cell, memory material aspects 2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material having simple binary metal oxide structure 2213/34 . Material including silicon 2213/35 . Material including silicon 2213/36 . Material including an oxide or a nitride 2213/37 . Material including carbon, e.g. graphite, grapheme 2213/36 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer. 2216/10 221				device being not part of a word line or a bit line
2213/19 . Memory cell comprising at least a nanowire and only two terminals 2213/30 . Resistive cell, memory material aspects 2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material including simple binary metal oxide structure 2213/33 . Material including silicon 2213/35 . Material including silicon 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including a tunneling barrier layer or a less doped memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 . Array wherein the substrate, the cell, the conductors and the access device are all made up of organic materials esh for again candinate up of organic materials esh tines, are made of nanowires 2213/81 . Array wherein the access device are all made up of organic materials be if organic materials esh tines, are made of nanowires 2213/82 . Array wherein the substrate, the cell, the conductors, e.g. word lines, bit lines, are made of nanowires 2213/80 . Array wherein the access device are all made up of organic materials abit line and a plate or source line receiving different potentials 2213/80 . Array wherein the substrate, sell and up of organic materials abit lines,	2213/18			
only two terminals Resistive cell, memory material aspects 2213/31	2212/10		2213/79	
2213/30 . Resistive cell, memory material aspects 2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material having simple binary metal oxide structure 2213/33 . Material including silicon 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 . Material having complex metal oxide, e.g. 2213/82 . Array wherein the array conductors, e.g. word lines, bit lines, are made of nanowires 2213/82 . Array wherein the array conductors, e.g. word lines, bit lines, are made of nanowires 2213/82 . Array wherein the array conductors, e.g. word lines, bit lines, are made of nanowires 2213/82 . Array wherein the array conductors, e.g. word lines, at the array conductors, e.g. word lines, at the array conductors, e.g. word lines, bit lines, are made of nanowires 2213/82 . Array wherein the array conductors, e.g. word lines, at the site in the storace in an internal source made of nanowires 2213/82 . Array wherein the array conductors, e.g. word lines, at the site in the storace in an internal source from a bit line and a plate or source line receiving different potentials 2216/00 . Structural aspects of erasable programmable read-only memories 2216/04 . Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory 2216/10 . Floating gate memory cells with a single polysilicon layer 2216/10 . Floating gate memory ce	2213/19		2213/80	
2213/31 . Material having complex metal oxide, e.g. perovskite structure 2213/32 . Material including silicon 2213/33 . Material including silicon 2213/35 . Material including silicon 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 . Carry wherein the array conductors, e.g. word lines, bit lines, are made of nanowires 2213/82 . Array having, for accessing a cell, a word line, a bit line and a plate or source line receiving different potentials 2216/00 Indexing scheme relating to G11C 16/00 and subgroups, for features not directly covered by these groups 2216/02 . Structural aspects of erasable programmable read-only memories 2216/04 . Nonvolatile memory cell provided with a separate control gate for erasing the cells, i.e. erase gate, independent of the normal read control gate consists of multiple isolated silicon islands, e.g. nanocrystals 2216/08 . Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory 2216/10 . Floating gate memory cells with a single polysilicon layer 2216/12 . Reading and writing aspects of erasable programmable read-only memories 2216/14 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory	2212/20	•		
perovskite structure 2213/32				
2213/32 . Material having simple binary metal oxide structure 2213/33 . Material including silicon 2213/34 . Material including silicon 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 . Structure including two electrodes, a memory active layer and at least two other layers or one or reservoir layer or a less doped memory active layer 2216/14 . Structure including two electrodes, a memory active layer and at least two other layers or or reservoir layer or a less doped memory active layer 2216/14 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 . Structure including a tunneling barrier layer, the memory ells with a single polysilicon layer 2216/12 . Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory 2216/12 . Floating gate memory cells with a single polysilicon layer 2216/12 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory. Typically a complete row or word line in flash memory 2216/16 . Flash programming of all the cells in an array,	2213/31		2213/81	
2213/33 Material including silicon 2213/34 Material includes an oxide or a nitride 2213/35 Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 Structure characterized by the electrode material, shape, etc. 2213/53 Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory. 2216/16 . Flash programming of all the cells in an array,	2213/32	-	2212/92	
2213/33 . Material including silicon 2213/34 . Material includes an oxide or a nitride 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/12 . Reading and writing aspects of erasable programmable read-only memories 2216/04 . Nonvolatile memory cell provided with a separate control gate for erasing the cells, i.e. erase gate, independent of the normal read control gate consists of multiple isolated silicon islands, e.g. nanocrystals 2216/08 . Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory 2216/10 . Floating gate memory cells with a single polysilicon layer 2216/12 . Reading and writing aspects of erasable programmable read-only memories 2216/14 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory 2216/16 . Flash programming of all the cells in an array,	2213/32		2213/82	
2213/34 . Material includes an oxide or a nitride 2213/35 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory 2216/16 . Flash programming of all the cells in an array,	2213/33			-
2213/55 . Material including carbon, e.g. graphite, grapheme 2213/50 . Resistive cell structure aspects 2213/51 . Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 . Structure characterized by the electrode material, shape, etc. 2213/53 . Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 . Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 . Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 . Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory 2216/16 . Flash programming of all the cells in an array,	2213/34	Material includes an oxide or a nitride		
grapheme 2213/50			2216/00	
2213/51 • Resistive cell structure aspects 2213/51 • Structure including a barrier layer preventing or limiting migration, diffusion of ions or charges or formation of electrolytes near an electrode 2213/52 • Structure characterized by the electrode material, shape, etc. 2213/53 • Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 • Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 • Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/14 • Structural aspects of erasable programmable read-only memories 2216/04 • Nonvolatile memory cell provided with a separate control gate for erasing the cells, i.e. erase gate, independent of the normal read control gate consists of multiple isolated silicon islands, e.g. nanocrystals 2216/08 • Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory 2216/10 • Floating gate memory cells with a single polysilicon layer 2216/10 • Reading and writing aspects of erasable programmable read-only memories 2216/12 • Reading and writing aspects of erasable programmable read-only memories 2216/14 • Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory 2216/16 • Flash programming of all the cells in an array,				
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2213/52 • Structure characterized by the electrode material, shape, etc. 2213/53 • Structure wherein the resistive material being in a transistor, e.g. gate 2213/54 • Structure including a tunneling barrier layer, the memory effect implying the modification of tunnel barrier conductivity 2213/55 • Structure including two electrodes, a memory active layer and at least two other layers which can be a passive or source or reservoir layer or a less doped memory active layer 2216/10 • Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory 2216/16 • Floating gate for erasing the cells, i.e. erase gate, independent of the normal read control gate source or layer speed. 2216/06 • Floating gate cells in which the floating gate consists of multiple isolated silicon islands, e.g. nanocrystals • Nonvolatile memory wherein data storage is accomplished by storing relatively few electrons in the storage layer, i.e. single electron memory • Floating gate memory cells with a single polysilicon layer • Reading and writing aspects of erasable programmable read-only memories • Circuits or methods to write a page or sector of information simultaneously into a nonvolatile memory, typically a complete row or word line in flash memory • Flash programming of all the cells in an array,			2216/04	•
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memory, typically a complete row or word line in flash memory 2216/16 . Flash programming of all the cells in an array,			2216/14	
flash memory 2216/16 . Flash programming of all the cells in an array,				
2216/16 • Flash programming of all the cells in an array,				
			221-11	
			2216/16	

2216/18	Flash erasure of all the cells in an array, sector or block simultaneously
2216/20	• Suspension of programming or erasing cells in an array in order to read other cells in it
2216/22	Nonvolatile memory in which reading can be carried out from one memory bank or array whilst a word or sector in another bank or array is being erased or programmed simultaneously
2216/24	Nonvolatile memory in which programming can be carried out in one memory bank or array whilst a word or sector in another bank or array is being erased simultaneously
2216/26	Floating gate memory which is adapted to be one-time programmable [OTP], e.g. containing multiple OTP blocks permitting limited update ability
2216/28	• Floating gate memory programmed by reverse programming, e.g. programmed with negative gate voltage and erased with positive gate voltage or programmed with high source or drain voltage and erased with high gate voltage
2216/30	• Reduction of number of input/output pins by using a serial interface to transmit or receive addresses or data, i.e. serial access memory
2229/00	Indexing scheme relating to checking stores for
2229100	correct operation, subsequent repair or testing
	stores during standby or offline operation
2229/70	Indexing scheme relating to G11C 29/70, for implementation aspects of redundancy repair
2229/72	Location of redundancy information
2229/723	• • Redundancy information stored in a part of the memory core to be repaired
2229/726	Redundancy information loaded from the outside into the memory
2229/74	Time at which the repair is done
2229/743	After packaging
2229/746	Before packaging
2229/76	Storage technology used for the repair
2229/763	E-fuses, e.g. electric fuses or antifuses, floating
	gate transistors
2229/766	Laser fuses